AMENDMENTS TO THE CLAIMS:

The listing of claims will replace all prior versions, and listings of claims in the application:

LISTING OF THE CLAIMS

- 1. Cancel.
- 2. (Currently Amended) The process according to claim [[1]] <u>22</u> wherein Xⁿ is selected from the group consisting of chloride, bromide, fluoride, sulfate, acetate, and tetrafluoroborate.
- 3. (Currently Amended) The process according to claim [[1]] <u>22</u> wherein the bath further comprises alloying metal ions, and electrodepositing nickel onto the metal substrate comprises electrodepositing a nickel-alloy onto the metal substrate.
- 4. (Currently Amended) An aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising:
 - a) nickel ions; and
 - b) an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or $[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and X^{n-} is an n-valent inorganic or organic anion and n = 1 or 2.

- 5. (Currently Amended) An aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising:
 - a) nickel ions;
 - b) at least one Class I brightener; and
 - c) an additive having the general formula:

$[H_2C=CHCH_2N^+R_1R_2R_3]_nX^{n-1}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and X^{n-1} is an n-valent inorganic or organic anion and n = 1 or 2.

- 6. (Currently Amended) An aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising:
 - a) nickel ions;
 - b) at least one Class II brightener; and
 - c) an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or $[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and X^{n-1} is an n-valent inorganic or organic anion and n = 1 or 2.

- 7. (Currently Amended) An aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising:
 - a) nickel ions;
 - b) at least one Class I brightener;
 - c) at least one Class II brightener; and
 - d) an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or $[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and X^{n-1} is an n-valent inorganic or organic anion and n=1 or 2.

- 8. (Currently Amended) An aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising:
 - a) nickel ions;

- b) alloying metal ions;
- c) at least one Class I brightener;
- d) at least one Class II brightener; and
- e) an additive having the general formula:

 $H_2C=CHCH_2NR_1R_2$ or $[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and X^{n-1} is an n-valent inorganic or organic anion and n = 1 or 2.

- 9. (Previously Presented) The bath according to claim 8 wherein the alloying metal ions are selected from the group consisting of iron, cobalt, tin, and zinc.
- 10. (Previously Presented) The bath according to claim 4 wherein Xⁿ is selected from the group consisting of chloride, bromide, fluoride, sulfate, acetate, and tetrafluoroborate.
- 11. (Previously Presented) The process according to claim 3, wherein the alloying metal ions are selected from the group consisting of iron, cobalt, tin, and zinc.
- 12. (Previously Presented) The aqueous acidic plating bath according to claim 4, wherein the additive comprises diallylamine.
- 13. (Previously Presented) The aqueous acidic plating bath according to claim 4, wherein the additive comprises triallylamine.
- 14. (Previously Presented) The aqueous acidic plating bath according to claim4, wherein the additive comprises diallyldimethyl ammonium chloride.
- 15. (Previously Presented) The aqueous acidic plating bath according to claim 4, wherein the additive is present in an amount of from about 5 mg/l to about 160 mg/l.

- 16. (Previously Presented) The aqueous acidic plating bath according to claim 4, wherein the additive is present in an amount of from about 5 mg/l to about 100 mg/l.
- 17. (Previously Presented) The aqueous acidic plating bath according to claim 4, wherein the additive is present in an amount of from about 6 mg/l to about 80 mg/l.
- 18. (Currently Amended) The process according to claim [[1]] <u>22</u>, wherein the additive comprises diallylamine.
- 19. (Currently Amended) The process according to claim [[1]] <u>22</u>, wherein the additive comprises triallylamine.
- 20. (Currently Amended) The process according to claim [[1]] <u>22</u>, wherein the additive comprises diallyldimethyl ammonium chloride.
 - 21. Cancel.
- 22. (Previously Presented) A process for the electrodeposition of a nickel or nickel-alloy coating on a substrate, the process comprising:

immersing a metal substrate in a bath comprising nickel ions and an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or $[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting of hydrogen, methyl, ethyl, propyl, allyl, propanediol and combinations thereof; and X^{n-} is an n-valent inorganic or organic anion and n equals 1 or 2; and

electrodepositing nickel onto the metal substrate.